

# MS AF REPLY UNDER 37 C.F.R. § 1.116 EXPEDITED PROCEDURE EXAMINING GROUP 2814

PATENT 0763-0173P

## IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Dong K. SOHN et al. Conf.:

9674

Appl. No.: 10/620,608

Group:

2814

Filed:

July 17, 2003

Examiner: Long Pham

For:

METHOD OF FORMING FILM FOR REDUCED OHMIC CONTACT

RESISTANCE AND TERNARY PHASE LAYER AMORPHOUS

DIFFUSION BARRIER

# LARGE ENTITY TRANSMITTAL FORM FOR REPLY AFTER FINAL UNDER 37 C.F.R. § 1.116

#### MS AF

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 October 28, 2004

### Sir:

Transmitted herewith is an amendment in the above-identified application.

The enclos	sed document	is	being	transm	itted	via	the	Certificate
of Mailing	g provisions	of	37 C.	F.R. §	1.8.			

The enclosed document is being transmitted via facsimile.

The fee has been calculated as shown below:

	CLAIMS REMAINING AFTER AMENDMENT		HIGHEST NUMBER PREVIOUSLY PAID FOR		PRESENT EXTRA	RATE	ADDITIONAL FEE .
TOTAL	5	-	20	=	0	\$ 18	\$0.00
INDEPENDENT	2	-	3	=	0	\$ 88	\$0.00
FIRST PRESE	FIRST PRESENTATION OF A MULTIPLE DEPENDENT CLAIM					\$300	\$0.00
						TOTAL	\$0.00

	Petition for ( ) month(s) extension of time pursual $37 \text{ C.F.R. } \$\$ 1.17$ and $1.136(a)$ . $\$0.00$ for the extenstime.	
$\boxtimes$	No fee is required.	
	Check(s) in the amount of \$0.00 is(are) enclosed.	
	Please charge Deposit Account No. 02-2448 in the amo \$0.00. This form is submitted in triplicate.	unt o
over requ	If necessary, the Commissioner is hereby authorized in acurrent, and future replies, to charge payment or cred expayment to Deposit Account No. 02-2448 for any additional uired under 37 C.F.R. §§1.16 or 1.17; particularly, extensite fees.	it an
	Respectfully submitted,	
	BIRCH, STEWART, KOLASCH & BIRC	H, LLI
	By	74( 
	P.O. Box 747  S/CAM/bsh Falls Church, VA 22040-0747  (3-0173P (703) 205-8000	

Attachment(s)



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37 C.F.R. § 1.116 EXPEDITED PROCEDURE

EXAMINING GROUP 2814

PATENT 0763-0173P

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REPLY AFTER FINAL UNDER 37 C.F.R. § 1.116

## MS AF

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 October 28, 2004

Sir:

In reply to the outstanding Office Action dated August 2, 2004, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

This reply includes: amendments to the specification, claims and remarks.